



IN THE UNITED STATES PATENTS AND TRADEMARK OFFICE

Applicant : Akira NAKASHIMA et al.

Title : COATING LIQUID FOR FORMING AMORPHOUS SILICA-BASED COATING FILM WITH LOW DIELECTRIC CONSTANT

Serial No. : 10/533,302

Filed : June 16, 2005

Group Art Unit : 1755

Examiner : McDONOUGH, JAMES E

Hon. Commissioner for Patents
P.O. Box 1450, Alexandria, VA 22313-1450

November 5, 2007

RESPONSE TO FINAL ACTION

Sir:

In the final Action of August 6, 2007, claims 1-10 and 29-35 were rejected under 35 U.S.C. 103(a) as being unpatentable over Komatsu et al. in view of Raman et al. in view of Senderov et al. in further view of Taguchi et al.

However, the applicants completely disagree with the rejections in the final Action, as explained below.

1. Differences between each cited reference and the application

a) Komatsu et al.

Komatsu, et al. discloses "a silica-based coating film with a low dielectric constant having a polymer composition comprising (i) hydrolyzate of alkoxysilane expressed by a general formula $X_nSi(OR)_{4-n}$ and/or halogenated silane expressed by a general formula $X_nSiX'_{4-n}$; and (ii) a readily decomposable resin".